

	L #	Hits	Search Text	DBs
1	L1	403807	mask or photomask or reticle	US-PGPUB; USPAT; EPO; JPO
2	L2	7701	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO
3	L3	7392	"716"/\$.ccor.	US-PGPUB; USPAT; EPO; JPO
4	L4	1	10/721522	US-PGPUB; USPAT; EPO; JPO
5	L5	747736	coarse fine	US-PGPUB; USPAT; EPO; JPO
6	L6	7701	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO
7	L7	1458	430/394.ccls.	US-PGPUB; USPAT; EPO; JPO
8	L8	139624	(electron or e) adj beam	US-PGPUB; USPAT; EPO; JPO
9	L9	8260	(focused adj ion) or fib	US-PGPUB; USPAT; EPO; JPO
10	L10	967041	shift or shifting or shifter or shifted	US-PGPUB; USPAT; EPO; JPO
11	L11	1385230	defect defective correct correction corrected	US-PGPUB; USPAT; EPO; JPO
12	L13	7370	evanescent	US-PGPUB; USPAT; EPO; JPO
13	L15	403807	mask or photomask or reticle	US-PGPUB; USPAT; EPO; JPO
14	L16	1661	L13 L15	US-PGPUB; USPAT; EPO; JPO
15	L17	7701	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO
16	L18	1458	430/394.ccls.	US-PGPUB; USPAT; EPO; JPO
17	L19	1326	L13.clm.	US-PGPUB; USPAT; EPO; JPO
18	L20	317	L16 L19	US-PGPUB; USPAT; EPO; JPO
19	L21	582	proximity adj field	US-PGPUB; USPAT; EPO; JPO
20	L24	317	L15 L20	US-PGPUB; USPAT; EPO; JPO
21	L26	1129930	expose\$	US-PGPUB; USPAT; EPO; JPO
22	L27	2954	L13 L26	US-PGPUB; USPAT; EPO; JPO

	L #	Hits	Search Text	DBs
23	L28	209	L20 L27	US-PGPUB; USPAT; EPO; JPO
24	L29	72506	L15.clm.	US-PGPUB; USPAT; EPO; JPO
25	L12	1	10/699873	US-PGPUB; USPAT; EPO; JPO
26	L14	1	L12 L13	US-PGPUB; USPAT; EPO; JPO
27	L22	2	L20 L21	US-PGPUB; USPAT; EPO; JPO
28	L23	6	L17 L21	US-PGPUB; USPAT; EPO; JPO
29	L25	4	L19 L21	US-PGPUB; USPAT; EPO; JPO
30	L30	52	L28 L29	US-PGPUB; USPAT; EPO; JPO